

In the Claims:

1. (Currently Amended) A substrate processing apparatus comprising:

a fluid-providing apparatus which is stationarily arranged adjacent a surface of at least one blow-off outlet, said fluid-providing apparatus having at least one fluid-providing path and said blow-off outlet provided for blowing off fluid from said at least one fluid-providing path, and

a rotating member capable of rotating about said fluid-providing apparatus,

wherein said rotating member comprises:

a first rotating member comprising a main surface that opposes one surface of a substrate to be processed, and a second rotating member being connected to said first rotating member and rotatably driven by a rotation-driving member,

wherein said fluid-providing apparatus and said at least one blow-off outlet are offset below the main surface of said first rotating member and fluid that is provided from said at least one fluid-providing path is flown from a gap between said surface of said fluid-providing apparatus and said main surface of said first rotating member,

and wherein a surface of said substrate is held contactlessly above the main surface of said first rotating member and said fluid-providing apparatus when fluid is blown off from said at least one blow-off outlet.

2. (Original) The substrate processing apparatus of claim 1, wherein the amount of the offset between a surface comprising said at least one blow-off outlet and said main surface of said first rotating member is about 2 mm or less.

3. (Currently Amended) The substrate processing apparatus of claim 1, wherein said fluid-providing apparatus comprises a cylindrical blow-off portion, on the surface of which said at least one blow-off outlet is provided, and a first seal portion for forming a non-contact seal between it, said first seal portion connected to said at least one fluid-providing path for receiving fluid and said first rotating member;

wherein said first rotating member comprises a through hole, in the center of which said blow-off portion is provided, and a second seal portion that fits said first seal portion;

and wherein a gap is formed between said blow-off portion and said through hole, and fluid that is provided with said first seal portion flows out from the gap.

4. (Original) The substrate processing apparatus of claim 3, wherein at least one shoulder portion having a radius smaller than a radius of said blow-off outlet is formed on the side of said blow-off outlet.

5. (Currently Amended)- A substrate processing apparatus comprising:

a fluid-providing means which is stationarily arranged and on the surface of which a plurality of blow-off outlets are provided for blowing off fluid; said fluid-providing means having a plurality of fluid-providing paths for providing fluid with said plurality of blow-off outlets and a rotating means which is capable of rotating about said fluid-providing means,

wherein said rotating means comprises:

a first rotating member comprising a main surface that opposes one surface of a substrate, and a second rotating member being connected to said first rotating member and rotatably driven;

and wherein said plurality of blow-off outlets comprise a first blow-off outlet located in the center, and at least one second blow-off outlet located about said first blow-off outlet, wherein a surface of said substrate can be contactlessly held above said first rotating member by blowing off gas from the first blow-off outlet, and liquid can be blown off from said second blow-off outlet to said substantially contactlessly held substrate,

and wherein fluid that is provided from the selected fluid-providing path is flown from a gap between said surface of said fluid-providing means and said main surface of said first rotating member.

6. (Original) The substrate processing apparatus of claim 5, wherein one surface of said substrate is cleaned by the liquid that is blown off from said second blow-off outlet.

7. (Original) The substrate processing apparatus of claim 5, wherein said second blow-off outlet located about said at least one first blow-off outlet comprises a plurality of second blow-off outlets.

8. (Original) The substrate processing apparatus of claim 5, wherein said substrate processing apparatus comprises a nozzle above said rotating means and is capable of providing liquid to a second surface that is opposite to said one surface of said contactlessly held substrate.

9. (Currently Amended) A substrate processing apparatus comprises:  
a fluid-providing apparatus having a first and a second diameters, wherein a plurality of blow-off outlets are formed on a surface of said first diameter and a first labyrinth seal portion is

formed on a surface of said second diameter, said first labyrinth seal having a plurality of annular convex or concave portions, the fluid-providing apparatus further comprising a providing port that is capable of providing fluid to at least said plurality of blow-off outlets;

and a rotating member being rotatably mounted to said fluid-providing apparatus;

wherein said rotating member comprises a main surface, in the center of which a through hole is formed,

wherein the surface of said first diameter of said fluid-providing apparatus is located in said through hole, and said rotating member further comprises a second labyrinth seal portion having a plurality of annular convex or concave portions that fits the first labyrinth seal portion;

wherein a first aperture is formed in said first labyrinth seal portion, and said first aperture is connected to said providing port through a first path;

and wherein a second aperture is formed in said second labyrinth seal portion, and said second aperture is connected to a second path, and said first aperture and said second aperture are spaced apart.

10. (Original) The substrate processing apparatus of claim 9, wherein the fluid provided from said providing port flows through said first path, said first aperture, and said first and second labyrinth seal portions and flows out from a gap between the surface of said first diameter and said through hole.

11. (Original) The substrate processing apparatus of claim 9, wherein said second aperture comprises a plurality of apertures, and said second path comprises a plurality of paths being connected to said plurality of apertures, and a plurality of fluid-draining outlets are formed on the

side of said rotating member, and said plurality of paths extend in radial directions and connected to said plurality of fluid-draining outlets respectively, and the fluid that is provided from said providing port flows through said first path, said first aperture, and said first and second labyrinth seal portions and can be drained out from said fluid-draining outlets through said second aperture and said second path.

12. (Original) The substrate processing apparatus of claim 9, wherein said substrate processing apparatus further comprises a liquid-providing nozzle above said rotating member, and is capable of providing liquid by said liquid-providing nozzle to a second surface that is opposite to a first surface of a substrate.

13. (Original) The substrate processing apparatus of claim 9, wherein said liquid-providing apparatus comprises a sensor for detecting the presence of a substrate.

14. (Currently Amended) A substrate processing apparatus comprising:

a holding plane comprising a surface, on which a plurality of blow-off outlets is formed and which is arranged stationary and an annular main surface that rotates about said surface, a gap formed between said surface and said main surface, said holding plane opposite to one surface of a substrate,

and a fluid-providing apparatus to provide fluid to said plurality of blow-off outlets, wherein, by contactlessly holding a surface of the substrate above said holding plane by fluid that is blown off from at least one blow-off outlet of said plurality of blow-off outlets, and wherein gas is flown from the gap by providing gas, and by blowing off cleaning chemical solutions from

at least one blow-off outlet of said plurality of blow-off outlets, one surface of the substrate that is held substantially contactlessly is cleaned.

15- 20. (Canceled)